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FR

1/1 - (C) WPI / DERWENT  
AN - 93-392425 [49]  
AP - JP920124233 920417  
PR - JP920124233 920417  
TI - Transparent electroconductive film coated glass mfr. - by forming  
electroconductive film on a glass substrate, forming a transparent  
oxide film with oxygen@ barrier properties, etc.  
it - TRANSPARENT ELECTROCONDUCTING FILM COATING GLASS MANUFACTURE FORMING  
ELECTROCONDUCTING FILM GLASS SUBSTRATE FORMING TRANSPARENT OXIDE FILM  
OXYGEN@ BARRIER PROPERTIES  
PA - (ASAG) ASAHI GLASS CO LTD  
PN - JP5294673 A 931109 DW9349 C03C17/34 005pp  
IC - C03C17/34  
AB - J05294673 The glass is made by forming a transparent electroconductive  
film on a glass substrate, forming a transparent oxide film having O2  
barrier properties on the transparent electroconductive film, followed  
by heat treating the glass substrate.  
- USE - Used for making transparent electroconductive film coated bent

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glass or coated tempered glass.  
- (Dwg.1/1)

24/28 (3/7 PAJ) - (C) PAJ / JPO  
PN - JP5294673 - 931109  
PA - ASAHI GLASS CO LTD

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I - C03C17/34

TI - PRODUCTION OF GLASS COATED WITH TRANSPARENT ELECTRICALLY CONDUCTIVE FILM

AB - PURPOSE: To reduce the resistance by forming a transparent electrically conductive film on a glass substrate, then forming a transparent metallic oxide film having oxygen barrier properties thereon and subsequently heat-treating the top surface of the glass substrate within a specific temperature range.

- CONSTITUTION: A transparent electrically conductive film 2 having a prescribed thickness is formed on a glass substrate 1 by using In<sub>2</sub>O<sub>3</sub> containing Sn, SnO<sub>2</sub> containing Sb or F or ZnO containing Al, etc., as a raw material according to an ion plating method for evaporating the raw material with an arc discharge plasma stream. Sputtering is then carried out on the transparent electrically conductive film 2 with a mixed gas of O<sub>2</sub>/Ar by using one or more of Sn, Zn, Ta, Nb, Cr, Si, Al and Zr as a target to form a transparent metallic oxide film 3 having a prescribed thickness and oxygen barrier properties. The resultant film is subsequently heat-treated at 300-750

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deg.C in the air to afford the objective transparent electrically conductive film-coated glass with hardly any rise in resistance even when bending or oxidation treatment is carried out.